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<b>Substitute for form 1449 INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (use as many sheets as necessary)				<b>Complete if Known</b>	
				<b>Application Number</b>	10/018,406
				<b>Filing Date</b>	December 13, 2001
				<b>First Named Inventor</b>	Charles E. Wickersham, Jr.
				<b>Art Unit</b>	1742
				<b>Examiner Name</b>	
<b>Sheet</b>	<b>1</b>	<b>of</b>	<b>4</b>	<b>Attorney Docket Number</b>	TSO 190 P2

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number Number - Kind Code <sup>2</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
MA		US-2,790,216	4-30-1957	Hunter	
MA		US-4,054,173	10-18-1977	Hickam	
MA		US-4,568,007	2-4-1986	Fishler	
MA		US-5,160,388	11-3-1992	Legresy et al.	
MA		US-5,369,063	11-29-1994	Gee et al.	
MA		US-5,406,850	4-18-1995	Bouchard et al.	RECEIVED APR 03 2002 TQ 1700
MA		US-5,559,614	9-24-1996	Urbish et al.	
MA		US-5,636,681	6-10-1997	Sulzer et al.	
MA		US-5,738,767	4-14-1998	Coad et al.	
MA		US-5,827,409	10-27-1998	Iwata et al.	

FOREIGN PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document Country - Number <sup>4</sup> -KindCode <sup>5</sup> Code <sup>3</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
MA		EP 0 211 401 B1	05-06-1992	General Electric Company	
MA		EP 0 418 846 B1	02-08-1995	Honeywell, Inc.	
MA		EP 0 665 193 A2	08-02-1995	Intevac, Inc.	
MA		EP 0 467 659 B1	03-06-1996	Sharp Kabushiki Kaisha	

Examiner Signature	Melvyn Andrews	Date Considered	11-20-03
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

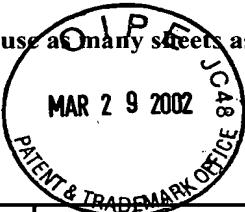
<sup>1</sup>Applicant's unique citation designation number (optional). <sup>2</sup>See Kinds Codes of USPTO Patent Documents at [www.uspto.gov](http://www.uspto.gov) or MPEP 901.04.

<sup>3</sup>Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup>Applicant is to place a check mark here if English language Translation is attached.

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MQ		US-5,887,481	3-30-1999	Leroy et al.	
MA		US-5,943,559	8-24-1999	Maeda	
MA		US-5,955,673	9-21-1999	Leroy et al.	
MA		US-5,989,782	11-23-1999	Nishiki et al.	
MA		US-6,001,227	12-14-1999	Pavate et al.	
		US-6,017,779	1-25-2000	Miyasaka <del>DUPLICATE</del>	RECEIVED APR 03 2002 TC 1700
MA		US-6,019,657	2-1-2000	Chakvorty et al.	
MA		US-6,020,946	2-1-2000	Callegari et al.	
MA		US-6,057,557	5-2-2000	Ichikawa	
MD		US-6,139,701	10-31-2000	Pavate et al.	

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MA		EP 0 412 843 B1	05-29-1996	Sharp Kabushiki Kaisha	
MA		EP 0 561 161 B1	04-23-1997	Corning Incorporated	
MA		WO 99/64854	12-16-1999	Tosoh SMD, Inc.	
MA		WO 00/15863	3-23-2000	Tosoh SMD, Inc.	

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				<b>Art Unit</b>	1752
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<b>Sheet</b>	<b>4</b>	<b>of</b>	<b>4</b>	<b>Attorney Docket Number</b>	TSO 190 P2

**INFORMATION DISCLOSURE STATEMENT BY APPLICANT**  
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<b>OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS</b>				
<b>Examiner Initials*</b>	<b>Cite No.<sup>1</sup></b>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published		<b>T<sup>2</sup></b>
		*BARNES, M.S. et al., <i>Phys. Rev. Letter</i> , (1992) 68, 313.		
		*GOREE J. et al., <i>J. Vac. Sci. Technol.</i> , (1992) A10, 3540.		
		*NADEL, S.J. et al., <i>35th Tech. Conf. Proc. Society of Vacuum Coaters</i> , (1992) 365.		
		*ANDERSON, L., <i>35th Tech. Conf. Proc. Society of Vacuum Coaters</i> , (1992) 325.		
		*SCHOLL, R.A., <i>37th Tech. Conf. Proc. Society of Vacuum Coaters</i> , (1994) 312.		
		*BAILEY, R.S. et al., <i>VMIC Conference, ISMIC</i> , (1994) 317.		
		*LEE, F. et al., <i>Microcontamination</i> , (1994) 12, 33.		
<i>Ma</i>		DANOVICH, D. et al., "Sputtering Issues for Flat-Panel Displays," <i>Information Display</i> , (November 1995), pp. 26-27, 30-31.		
		*TAKAHASHI, K.M. et al., <i>J. Vac. Sci. Technol.</i> , (1996) A14, 2983.		
		*SELWYN, G.S. et al., <i>J. Vac. Sci. Technol.</i> , (1997) A15, 2023.		
		*EERNISSE, E.P. et al., <i>J. Appl. Phys.</i> , (1997) 48, 91		
		*MONTEIRO, O.R. et al., <i>IEEE Trans. Plasma Science</i> , (1999) 27, 1030.		
		*ABBURI, M. et al., <i>Solid State Technology</i> , (1999) 42, 55.		

<b>Examiner Signature</b>	<i>Melvyn Andrews</i>	<b>Date Considered</b>	<i>11-20-03</i>
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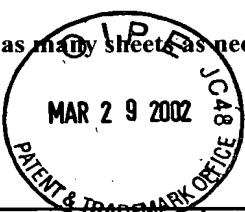
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 <b>MAR 29 2002</b> <small>PATENT &amp; TRADEMARK OFFICE &amp; CVC</small>				<b>First Named Inventor</b>	Charles E. Wickersham, Jr.
				<b>Art Unit</b>	1752
				<b>Examiner Name</b>	
<b>Sheet</b>	3	of	4	<b>Attorney Docket Number</b>	TSO 190 P2

<b>OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS</b>					
Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published			
		T <sup>2</sup>			
		*SELWYN, G.S. et al., <i>Appl.Phys. Letter</i> , (1876) p. 57.			
		*VON GÜNTHERSCHULZE, A., <i>Z. Physik</i> , (1933) 86, 778.			
		*FREITAG, W.O. et al., <i>2nd Symposium on Deposition of Thin Films by Sputtering</i> , CVC, Rochester, NY, (June 1967) p. 92.			
		*ROBINSON, I.E. et al., <i>J. Nuclear Mat.</i> , (1976) 63, 432.			
		*WEINER, G.K., <i>J. Vac. Sci. Technol.</i> , (1985) A3, 1821.			
		*ROTH, R.M. et al., <i>Appl. Phys. Letter</i> , (1985) 46, 253.			
		*SPEARS, K.G. et al., <i>IEEE Trans. Plasma Sci.</i> , (1986) PS-14, 179.			
		*SELWYN, G.S. et al., <i>J. Vac. Sci. Technol.</i> , (1989) A7, 2758.			
		*JELLMU, G.M. et al., <i>J. Appl. Phys.</i> , (1990) 67, 6490.			
		*ANDERSON, H.M. et al., <i>J. Applied Physics</i> , (1990) 67, 3999.			
		*SELWYN, G.S. et al., <i>J. Vac. Sci. Technol.</i> , (1990) A8, 1726.			
		*AKARI, K. et al., <i>Surf. Coatings &amp; Technol.</i> , (1990) 43-44, 312.			
		*SMADJ, M.M. et al., <i>J. Vac. Sci. Technol.</i> , (1992) B10, 30.			
		LOGAN, J.S. et al., <i>J. Vac. Sci. Technol.</i> , (1992) A10, 1875.			
		*YOO, W.J. et al., <i>Appl. Phys. Letter</i> , (1992) 60, 1073.			
MA		FOSTER, H.H. et al., "A Modular Approach to Sputter Coating of Flat Panel Displays," <i>Society of Vacuum Coaters 35th Annual Technical Conference</i> (1992) pp. 357-361.			

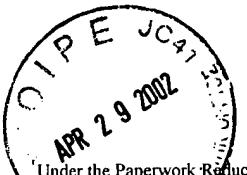
Examiner Signature	Melvyn Andrews	Date Considered	11-20-03
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Substitute for form 1449A/PTO				Complete if Known	
<b>SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (use as many sheets as necessary)				Application Number	10/018,406
Sheet	1	of	3	Filing Date	December 13, 2001
				First Named Inventor	Charles E. Wicksell, Jr.
				Art Unit	1752
				Examiner Name	MAY 2 RECEIVED TC 1700 2002
				Attorney Docket Number	TSO 190 P2

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MA		FREITAG, W.O. et al., "Diode Sputtering of Cermet Films," <i>2nd Symposium on Deposition of Thin Films by Sputtering</i> , University of Rochester and Consolidated Vacuum Corporation, Rochester, NY, June 1967, pp. 92-96.	
MA		ROBINSON, J.E. et al., "Models for Chunk Sputtering," <i>Journal of Nuclear Materials</i> , 1976, Vol. 63, pp. 432-437, North-Holland Publishing Company.	
MA		EERNISSE, E.P. et al., "Role of Integrated Lateral Stress in Surface Deformation of He-Implanted Surfaces," <i>Journal of Applied Physics</i> , January 1, 1977, Vol. 48, No. 1, pp. 9-17, American Institute of Physics.	
MA		ROTH, R.M. et al., "Spatial Dependence of Particle Light Scattering in an RF Silane Discharge," <i>Appl. Phys. Letter</i> , February 1, 1985, Vol. 46, No. 3, pp. 253-255, American Institute of Physics.	
MA		WEHNER, G.K., "Cone Formation as a Result of Whisker Growth on Ion Bombarded Metal Surfaces," <i>J. Vac. Sci. Techol.</i> , July/August 1985, A 3 (4), pp. 1821-1835, American Vacuum Society.	
MA		SPEARS, K.G. et al., "Particle Distributions and Laser-Particle Interactions in an RF Discharge of Silane," <i>IEEE Transactions on Plasma Science</i> , April 1986, Vol. PS-14, No. 2, pp. 179-187, IEEE.	
MA		SELWYN, G.S. et al., "In Situ Laser Diagnostic Studies of Plasma-Generated Particulate Contamination," <i>J. Vac. Sci. Technol.</i> , July/August 1989, A 7, (4) pp. 2758-2765, American Vacuum Society.	
MA		ANDERSON, H.M. et al., "Particulate Generation in Silane / Ammonia RF Discharges," <i>J. Applied Physics</i> , May 1, 1990, Vol. 67, No. 9, pp. 3999-4011, American Institute of Physics.	

Examiner Signature	Melvyn Andrews	Date Considered	11 - 20 - 03
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Substitute for form 27449A PTO				Complete if Known	
<b>SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (use as many sheets as necessary)				Application Number	10/018,406
Sheet	2	of	3	Filing Date	December 13, 2001
				First Named Inventor	Charles E. Wickersham, Jr.
				Art Unit	1752
				Examiner Name	MAY 2 2002 RECEIVED TSO 100 P2 1700
				Attorney Docket Number	TSO 100 P2 1700

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS		
Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published
MA		JELLUM, G.M. et al., "Particulates in Aluminum Sputtering Discharges," <i>J. Appl. Phys.</i> , May 15, 1990, Vol. 67 No. 10, pp. 6490-6496, American Institute of Physics.
MA		SELWYN, G.S. et al., "In situ Plasma Contamination Measurements by HeNe Laser Light Scattering: A Case Study," <i>J. Vac. Sci. Techol.</i> , May / June 1990, A 8, (3) pp. 1726-1731, American Vacuum Society.
MA		SELWYN, G.S. et al., "Particle Trapping Phenomena in Radio Frequency Plasmas," <i>Appl. Phys. Letter</i> , October 29, 1990, Vol. 57, No. 18 pp. 1876-1878, American Institute of Physics.
MA		AKARI, K. et al., "Reduction in Macroparticles During the Deposition of TiN Films Prepared by Arc Ion Plating," <i>Surface and Coatings Technology</i> , 1990, 43/44, pp. 312-323, Elsevier Sequoia, The Netherlands.
MA		BARNES, M.S. et al., "Transport of Dust Particles in Glow-Discharge Plasmas," <i>Physical Review Letters</i> , January 20, 1992, Vol. 68, No. 3, pp. 313-316, The American Physical Society.
MA		SMADI, M.M. et al., "Particle Contamination on a Silicon Substrate in a SF <sub>6</sub> / Ar Plasma," <i>J. Vac. Sci. Techol.</i> , January/February 1992, B 10, (1) pp. 30-36, American Vacuum Society.
MA		YOO, W.J. et al., "Kinetics of Particle Generation in Sputtering and Reactive Ion Etching Plasmas," <i>Appl. Phys. Letter</i> , March 2, 1992, Vol. 60, No. 9, pp. 1073-1075, American Institute of Physics.
MA		LOGAN, J.S. et al., "Study of Particle Emission in Vacuum from Film Deposits," <i>J. Vac. Sci. Techol.</i> , July/August 1992, A 10, (4) pp. 1875-1878, American Vacuum Society.
MA		GOREE J. et al., "Particulate Release from Surfaces Exposed to a Plasma," <i>J. Vac. Sci. Techol.</i> , November/December 1992, A 10, (6) pp. 3540-3544, American Vacuum Society.

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41/4

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MA		ANDERSON, L., "A New Technique for Arc Control in DC Sputtering," <i>Society of Vacuum Coaters 35th Annual Technical Conference Proceedings</i> , 1992, pp. 325-329.
MA		NADEL, S.J. et al., "Enhanced Chromium First Surface Mirrors," <i>Society of Vacuum Coaters, 35th Annual Technical Conference Proceedings</i> , 1992, pp. 365-369.
MA		SCHOLL, R.A., "A New Method of Handling Arcs and Reducing Particulates in DC Plasma Processing," <i>Society of Vacuum Coaters 37th Annual Technical Conference Proceedings</i> , 1994, pp. 312-315, Advanced Energy Industries, Inc.
MA		LEE, F. et al., "Detecting and Reducing Particles for LPCVD Silicon Nitride Deposition," <i>Microcontamination</i> , March 1994, Vol. 12, pp. 33-37, 76-77.
MA		BAILEY, R.S. et al., "Particle Emission from Al <sub>2</sub> O <sub>3</sub> Doped Aluminum Targets During Sputtering Deposition," <i>VMIC Conference, ISMIC</i> , June 7-8, 1994, p. 317.
MA		TAKAHASHI, K.M. et al., "Current Capabilities and Limitations of <i>In Situ</i> Particle Monitors in Silicon Processing Equipment," <i>J. Vac. Sci. Technol.</i> , November/December 1996, A 14, (6) pp. 2983-2993, American Vacuum Society.
MA		SELWYN, G.S. et al., "Particle Contamination Formation in Magnetron Sputtering Processes," <i>J. Vac. Sci. Technol.</i> , July/August 1997, A 15 (4), pp. 2023-2028, American Vacuum Society.
MA		MONTEIRO, O.R. et al., "Vacuum-Arc-Generated Macroparticles in the Nanometer Range," <i>IEEE Transactions on Plasma Science</i> , August 1999, Vol. 27, No. 4, pp. 1030-1033, IEEE.
M		ABBURI, M. et al., "Low-Defect Target Metallurgy Development for sub-0.18μm Al-based Interconnects," <i>Solid State Technology</i> , December 1999, Vol. 42, pp. 55-58, Solid State Technology.

Examiner Signature	Melvyn Andrews	Date Considered	11-20-03
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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